



# +/- RESIST STRIP & CLEAN

## MODEL RSSx133

### **DESCRIPTION: MODEL RSSx133**

The highly efficient Model RSSx133 is the ideal for Stripping and Cleaning Photoresist both Positive & Negative on Photomask, Wafers and Substrates. The very reliable and cost effective system utilizes proven assortment of cleaning technologies. The RSSx133 can be configured with several cleaning options from Brush for Sulfuric Peroxide, Surfactant, and/or DI-H<sub>2</sub>O; Megasonic Nozzle for DI-H<sub>2</sub>O or Chemistries; low pressure nozzles for chemistry dispenses; heaters for chemistries and DI-H<sub>2</sub>O; and much more. The Rapid and Effective Drying technique combines Variable Spin Speeds; optional Heated DI-H<sub>2</sub>O; and Nitrogen Assist. The System is very safe, having "Rinse to pH" before access to the substrate to minimize exposure to chemistries.

### **FEATURES: CONTROL & SAFETY**

- System Designed for Significant Control & Safety
- Up to Twenty (20) inches on the Diagonal/Diameter Substrate Compatibility or Multiples of Smaller Sizes.
- Main Spindle Assembly having DC Brushless Servo Motor for precise speed control & indexing.
- Adjustable Arm Speed and Travel Positions with Arms of Teflon Coated Stainless Steel.
- Radially Exhausted Chamber for Maximum Laminar Flow with N<sub>2</sub> feed at Top of the lid.
- DI-H<sub>2</sub>O Heater for Clean & Dry Assist.
- Process containment of chemically compatible material either PVDF or optional PTFE.
- Stand-alone Polypropylene Cabinet.
- Microprocessor Control Capable of Retaining Thirty (30) Recipes having thirty (30) Steps each in Memory. Both number of Recipes & Steps are expandable upon request.
- Built in Safety Interlocks & Double Containment.
- Rinse to pH of entire process area & substrate with interlocks to prohibit access to process area & control Drain and Spindle Speed till safe.
- Push Button Lid Open/Close.
- Touch Screen Graphic User Interface (GUI) with Ease of Programming & Security Lockouts with On-Screen Error Reporting.
- Drain Diverter Valves for Chemical & Rinse DI-H<sub>2</sub>O
- Designed to SEMI S2/S8 Guidelines



MODEL  
RSSx133



TYPICAL  
CLEANING  
CHAMBER  
& CHUCK

### **CHEMISTRY:**

- Nano-Strip<sup>®</sup>, Piranha: (H<sub>2</sub>SO<sub>4</sub> + H<sub>2</sub>SO<sub>5</sub> + H<sub>2</sub>O<sub>2</sub> + H<sub>2</sub>O)

### **OPTIONS: UP TO FOUR OSCILLATING DISPENSE ARMS**

- Various sizes & types of chucks for Wafers, Photomask, and other Substrates.
- Auto Up/Down Oscillating Adjustable Self Cleaning Brush Assembly for chemical, Surfactant, & DI-H<sub>2</sub>O Dispenses.
- Fixed or Oscillating Low Pressure Dispense with various Nozzles for DI-H<sub>2</sub>O &/or Chemistries.
- Chemical Cabinet with weight Scale Dispense Canisters & Pump.
- Heater for Chemical Dispenses.
- Secondary Containment With Leak Detection
- Oscillating Megasonic DI Water or Chemical Dispense Arm.
- FM4910 Fire Retardant Cabinet & Process Area Materials

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